

IN THE CLAIMS

Claims 1-10 (canceled)

11. (previously presented) A method for the operation of an in-line coating installation having an inward transfer chamber, an adjoining buffer chamber, a process chamber adjoining thereon, a further buffer chamber adjoining it and an outward transfer chamber adjoining it, with gates provided between the chambers, which can be opened and closed, and where the inward transfer chamber, the buffer chamber and the outward transfer chamber are developed as identical modules and for receiving substrates selected from the group consisting of flat architectural glass, a metal plate, an Si wafer a synthetic material plate and the like up to a specified maximum size, wherein for the coating of the substrates, which are greater than the modules, the gate between the inward transfer chamber and the buffer chamber as well as the gate between the buffer chamber and the outward transfer chamber are opened and the pressure conditions of the buffer chambers and of the inward transfer or outward transfer chamber are adapted to one another.

12. (previously presented) The method of claim 11, wherein the chambers are equipped with their own transport arrangements for substrates and the transport rates of these transport arrangements are matched to one another.

13. (previously presented) The method of claim 11, wherein the process chamber comprises at least two slit diaphragms, of which the one slit diaphragm forms a left boundary of the process chamber and the other slit diaphragm a right boundary of the process chamber.

14. (previously presented) The method of claim 11, wherein
the gate at the entrance to the first buffer chamber and the gate between the second buffer chamber and the outward transfer chamber are opened;

the gate at the entrance of the inward transfer chamber is opened;

a substrate of a length exceeding the length of the inward transfer chamber or of the buffer chamber is transported into the inward transfer chamber and the buffer chamber,

the gate at the entrance of the inward transfer chamber is closed,

the space formed by the inward transfer chamber and, with the gate at the entrance to the process chamber closed, the buffer chamber is evacuated to a specified pressure;

upon reaching a specified pressure, the gate at the entrance of the process chamber is opened;

the substrate is transported into the process chamber and the gate at the entrance of the process chamber is closed again,

the substrate is worked in the process chamber;

the gate at the exit of the process chamber is opened;

the worked substrate is moved into the space formed of the buffer chamber; and the outward transfer chamber;

the gate at the exit of the process chamber is closed;

the gate at the exit of the outward transfer chamber is opened;

the worked substrate is moved to the outside; and

the gate at the exit of the outward transfer chamber is closed.

15. (previously presented)The method of claim 14, wherein after the inward transfer of the substrate into the space formed of the inward transfer chamber and buffer chamber and, after the gate is closed, first the pumps associated with the inward transfer chamber carry out an evacuation from atmospheric pressure to a first specified pressure, and that subsequently the

pumps associated with the buffer chamber carry out an evacuation to a pressure corresponding approximately to the pressure of the process chamber.

16. (previously presented)The method of claim 15, wherein the pressure in the space formed of the inward transfer chamber and buffer chamber is lowered from atmospheric pressure first to approximately 7 mbar and, subsequently, the pressure in the same space is decreased to approximately 0.05 mbar.

17. (previously presented)The method of claim 11, wherein the transport arrangement of the inward transfer chamber and the transport arrangement of the adjoining buffer chamber are operated synchronously.

18. (previously presented)The method of claim 17, wherein the transport arrangement of the process chamber is operated at the same rate as the transport arrangements of the inward transfer chamber and the buffer chamber.

19. (previously presented)The method of claim 11, wherein in all chambers pressure meters are provided, whose pressure is queried by a control, and that this control carries out a switching action when specified pressures are reached.

20. (previously presented)The method of claim 19, wherein the switching action is the opening or closing of gates or the opening or closing of valves disposed between chamber and pump.

21. (new) A method for the operation of an in-line coating installation having an inward transfer chamber, an adjoining buffer chamber, a process chamber adjoining thereon, a further buffer chamber adjoining it and an outward transfer chamber adjoining it, with gates provided between the chambers, which can be opened and closed, and where the inward transfer chamber, the buffer chamber and the outward transfer chamber are developed as modules having identical dimensions and for receiving substrates selected from the group consisting of flat architectural glass, a metal plate, an Si wafer a synthetic material plate and the like up to a specified maximum size, wherein for the coating of the substrates, which are greater than the

modules, the gate between the inward transfer chamber and the buffer chamber as well as the gate between the buffer chamber and the outward transfer chamber are opened and the pressure conditions of the buffer chambers and of the inward transfer or outward transfer chamber are adapted to one another.